

ABSTRACT

The provided is a sputtering target material that is made not to cause an arcing phenomenon and splash phenomenon at the time of sputtering as completely as possible. A portion to be used for sputtering of the sputtering target material is subjected to a friction stir processing. Even with a sputtering target material made of a carbon-containing aluminum alloy or a large-sized sputtering target material, the arcing phenomenon and the splash phenomenon at the time of sputtering can be certainly suppressed.